Precisely targeted. Components for ion implantation.

From the smallest spare part through to the complete ion source. For all wafer diameters and production technologies: With more than 2 000 components for implanter systems, we are the world's largest second source supplier for ion implantation.

At Plansee California we are at work on graphite electrodes for ion implantation. In ion implanters, these electrodes help to form the ion beam which then impacts a silicon wafer.

This process for the manufacture of semiconductors takes place at high temperatures and in the presence of aggressive process gases and strong electromagnetic fields. For our components made of molybdenum, tungsten, graphite, ceramics and steel that's not a problem. These ensure that the electrons are generated at temperatures of up to 1 400 °C and then channeled precisely along the beam path.
Tell us what you want. We'll make it.

With our varied range of machining capabilities, you can choose the option that is perfect for you. Accurate to a hundredth of a millimeter and with more than 30 years of experience in the semiconductor industry, we produce components that conform precisely to the OEM standard or further develop your components at our production sites in Japan and the USA.

Cut costs. With our Advanced Standard.

For our customers, Plansee spare parts are often more than just spares. Taking the equipment manufacturer's original spare parts as our starting point, we optimize the geometries and material compositions.

The outstanding result:

- Lower cleaning costs
- Reduced maintenance work
- Reduced downtimes
- Simplified component installation and removal
- Longer service lives

Get to know us in person and talk to our experts to find out how you can benefit from a real improvement in the efficiency of your system.